

ABSTRACT OF THE DISCLOSURE

Disclosed is a plasma processing method, in which  
a process gas is introduced into an evacuated process  
chamber for subjecting a target object to a plasma  
processing. The plasma processing method is featured  
in that at least a part of the process gas exhausted  
from the process chamber is introduced again into the  
process chamber. A specified value is obtained by  
monitoring the state of the plasma of the process gas  
within the process chamber, and the introducing  
conditions of the process gas into the process chamber  
are controlled to adjust a predetermined property value  
to a regulated value.

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